In re Appln. of KUNITSUGU et al. Application No. Unassigned

ABSTRACT AMENDMENTS

Replace the Abstract with:

A semiconductor laser device includes a dielectric multilayer film with a reflectance of 40% or more, formed on at least one of optical exit faces of a laser chip, wherein the. The dielectric multilayer film includes a-dielectric film of tantalum oxide (Ta₂O₅) and another dielectric film of a dielectric oxide, such as aluminum oxide (Al₂O₃), and silicon oxide (SiO₂), the. The tantalum oxide film-having has an optical absorption coefficient smaller than that of silicon (Si)-film and thermal stability in emission superior to that of titanium oxide (TiO₂)-film, thereby remarkably improving the COD catastrophic optical damage degradation level of the laser chip.